

Development of ATLAS Pixel Detector for the HL-LHC

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TCHOU SYMPOSIUM

Overview

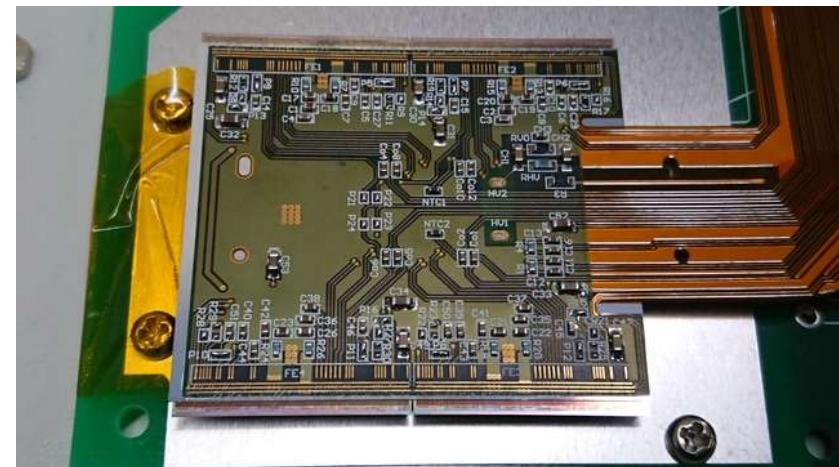
□ Introduction

- High luminosity LHC
- Radiation damage in silicon detectors

□ New Pixel detector for HL-LHC

- Detectors for HL-LHC
- Planner pixel sensor
- Biasing structure

□ Summary



□ High Luminosity LHC (2026)

- Instantaneous luminosity : $7.5 \times 10^{34} \text{ cm}^{-2}\text{s}^{-1}$
- Integrated luminosity : 3000 fb^{-1}
- Radiation damage : $1 \times 10^{16} \text{ 1MeV n}_{\text{eq}}\text{cm}^{-2}$
- Number of interaction : ~ 200 per crossing

➡ Increase **Radiation damage** and **Pile-up**

□ How can we maintain physics performances?

- Radiation Tolerance
- Fine Pixel
- High speed readout
- Trigger logic upgrade



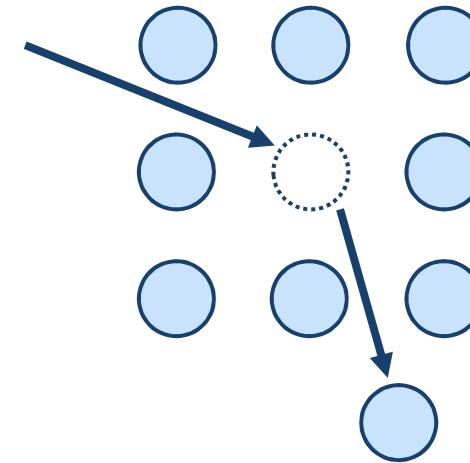
**New Silicon Tracker
(ITk Pixel and ITk Strip)**

are needed.

Radiation damage in Si detectors

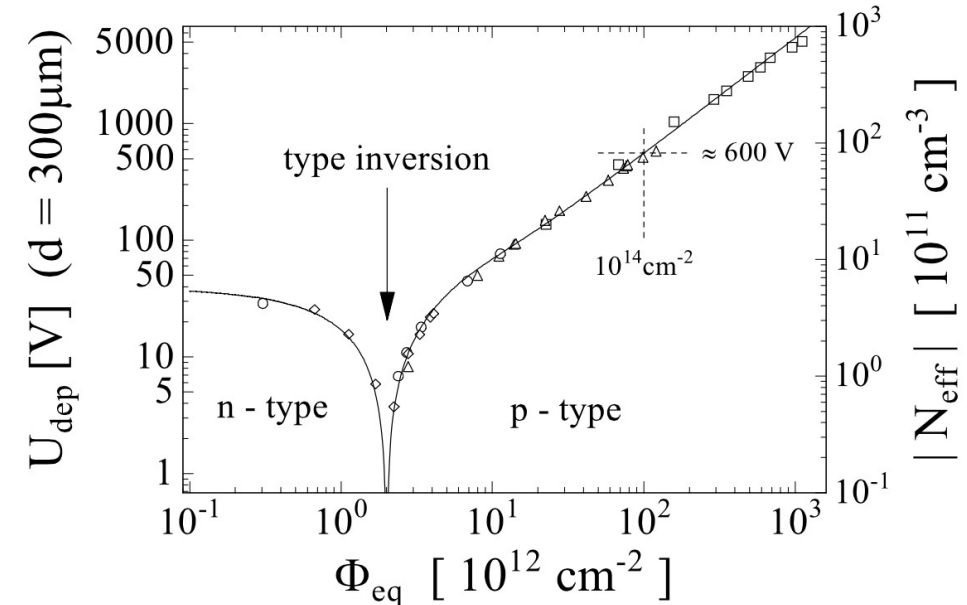
□ Bulk damage

- Main effect for Si sensors
- Collision with particles make defects
→ Many exogenous level will be created



□ Defect's effect

- Increase p-type impurity
→ **Higher depletion voltage**
- Recombination center
→ **Noise, leakage current**
- Trapping center
→ **Charge Collection Efficiency**



Detectors for HL-LHC

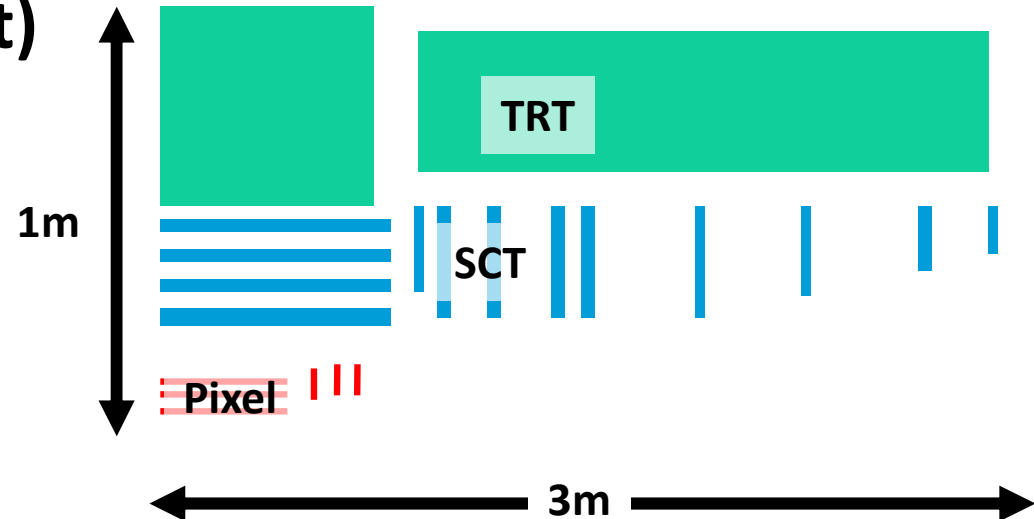
□ Inner Detector (current)

- Detector is composed of

- ✓ Pixel } **Silicon**
- ✓ SCT } **Silicon**
- ✓ TRT } **Gas**

- Silicon area : $\sim 65\text{m}^2$

- Channel : $\sim 100\text{M}$



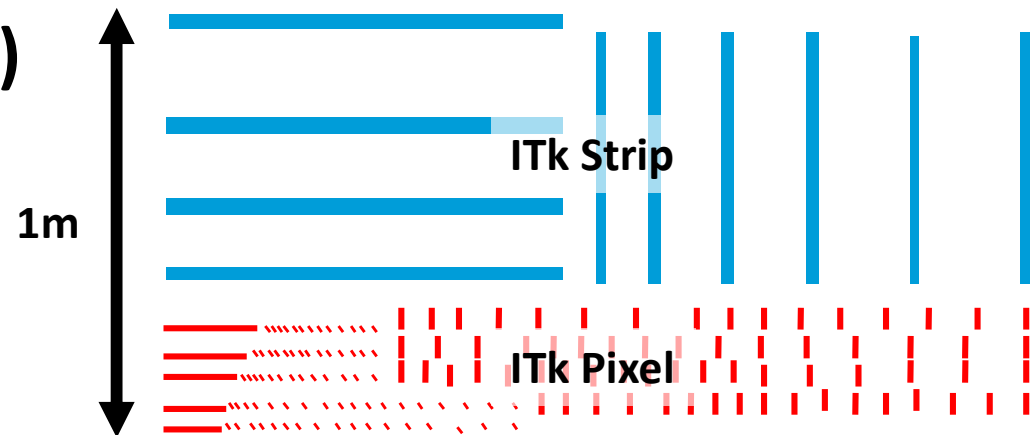
□ Inner Tracker (upgrade)

- Detector is composed of

- ✓ ITk Pixel } **All Silicon**
- ✓ ITk Strip } **All Silicon**

- Silicon area : $\sim 200\text{m}^2$

- Channel : $\sim 5\text{G}$

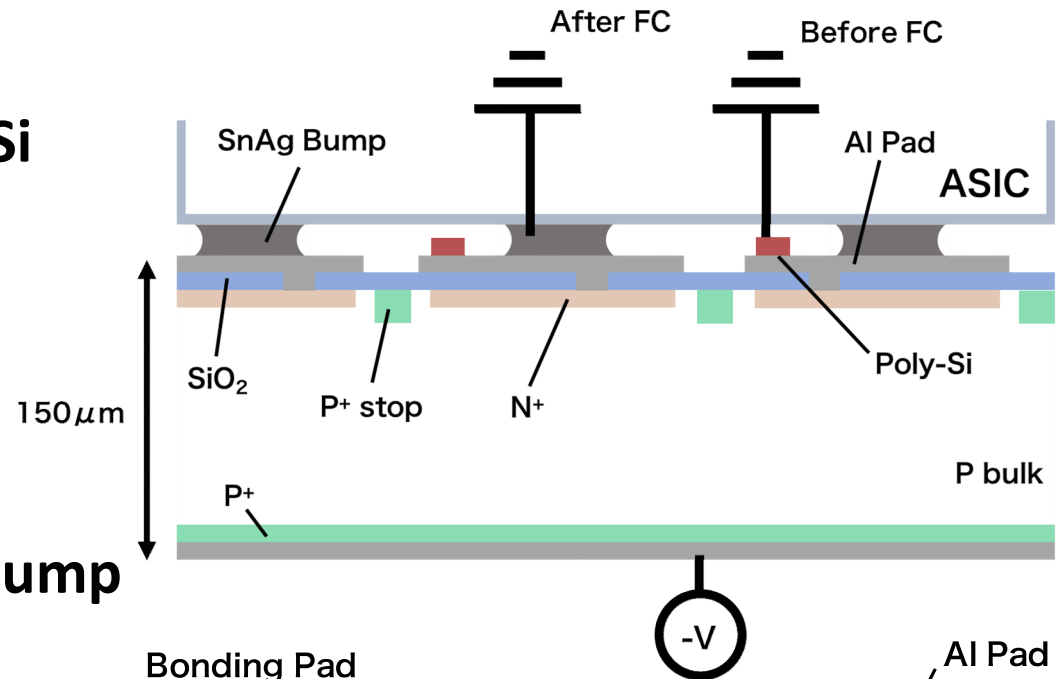


Cost is very important point

Planner Pixel Sensor

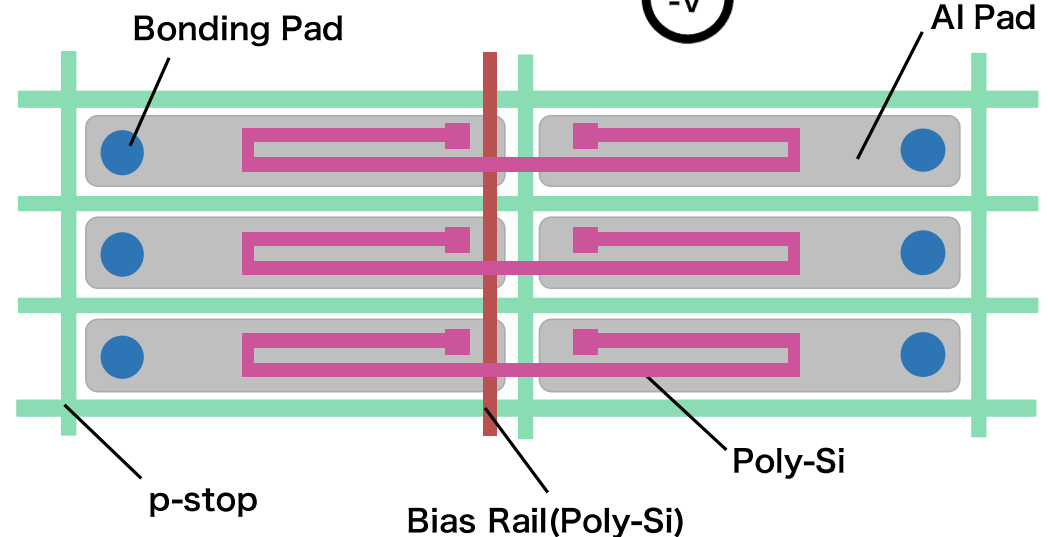
□ n⁺-in-p pixel sensor

- Implanting n⁺ into p-type Si
- Lower costs
- Radiation tolerance up to $\sim 3 \times 10^{15} \text{ 1MeV } n_{\text{eq}} \text{ cm}^{-2}$
- No type inversion
- Bond to ASIC with metal bump



□ Device structure

- Pixel Size
 - 50×50 or $25 \times 100 \mu\text{m}^2$
 - One of the most smallest planner hybrid sensor
- Biasing Structure



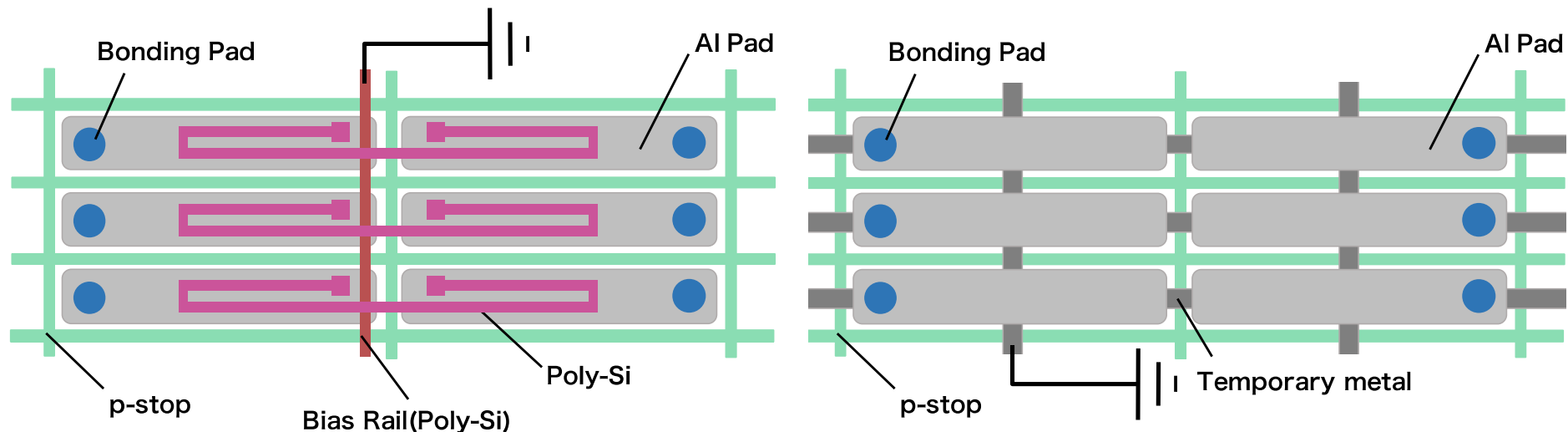
Biasing structures

□ IV-testing before bump-bonding

- Cost of bump-bonding is quite high (accounted for ~50%)
 - IV-testing before bump-bonding is important for good yield
- Need to set all pixel GND for biasing

□ How can we do? - two choices

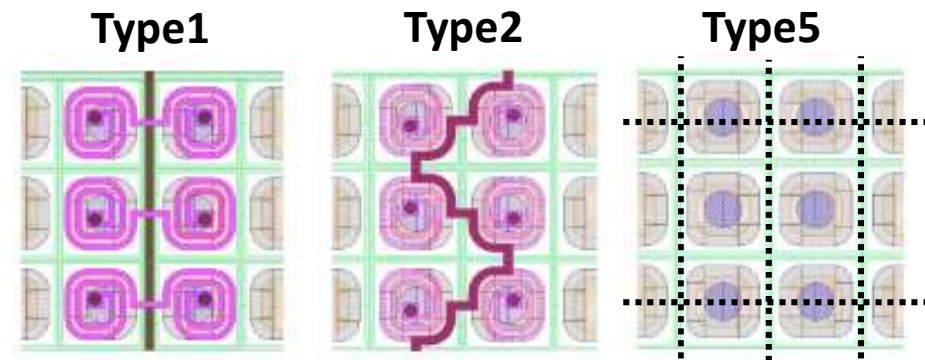
- Temporary metal : Metal structure (will be etching), high costs
- Bias rail : High resistivity Poly-Si rail, radiation damage issue



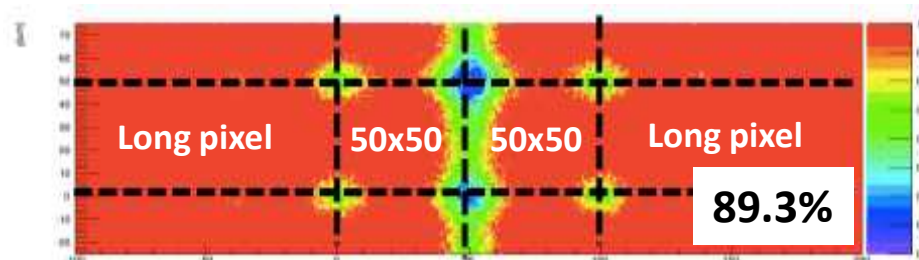
Bias rail structure

□ Efficiency drop after irradiation

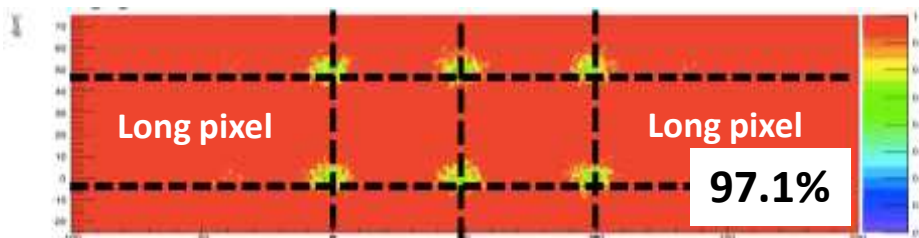
- Typical efficiency drop observed at under biasing structure
 - Changing concentrations of impurity and charge **collection field**
 - Some carrier induced on biasing structure (not electrode)
- Succeed to reduce efficiency drop by “Offset structure”



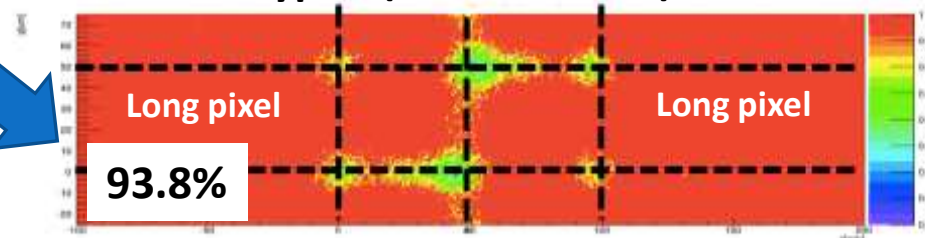
Type1 (no offset, 1000V)



Type5 (no structure, 1000V)



Type2 (offset, 1000V)



Efficiency value is improved by 4% !!

□ Development of ATLAS pixel detector

- ATLAS Inner detectors will be replaced with new silicon detectors for higher luminosity experiment. Need to maintain physics performance in high luminosity environment.
- We are developing finer pixel, with lower cost and higher radiation tolerance detector.
- Low cost can be materialized by IV-testing before bump-bonding.
- Biasing structures are needed. Efficiency drop of 3%(no-bias), 4%(with bias structure) is observed after irradiation.